

PATENT

Atty. Dkt. No. APPM003421.C2/PPC/ECP/CKIM

**IN THE CLAIMS:**

Please cancel claims 1-14, and 16-19 without prejudice, and amend the claims as follows:

1-14. (Cancelled)

15. (Currently Amended) ~~The deposition system of claim 10, An electrochemical deposition system, comprising:~~

a mainframe having a mainframe wafer transfer robot disposed therein;  
a loading station disposed in connection with the mainframe, wherein the loading station comprises one or more loading station robots;  
one or more processing stations disposed in connection with the mainframe, wherein each processing station comprises one or more electrochemical deposition cells; and  
one or more post deposition treatment chambers disposed in connection with the mainframe, wherein the one or more post deposition treatment chambers comprise one or more rapid thermal anneal chambers, one or more thermal anneal chambers, or a combination thereof.

16-19. (Cancelled)

20. (Currently Amended) ~~The deposition system of claim 19, An electrochemical deposition system, comprising:~~

a mainframe having a mainframe wafer transfer robots disposed therein;  
a loading station disposed in connection with the mainframe, wherein the loading station comprises one or more cassette receiving areas;  
two or more processing stations disposed in connection with the mainframe, wherein each processing station comprises two or more electrochemical deposition cells; and

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two or more post deposition treatment chambers in connection with the loading station, wherein the two or more post deposition treatment chambers comprise[[s]] one or more thermal anneal chambers and two or more spin-rinse-dry modules, wherein one or more loading station robots transfer wafers between the one or more cassette receiving areas and the two or more post deposition treatment chambers.